



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of YAMAMURA *et al.*

Appln. No.: 09/924,116

Group Art Unit: tbd

Filed: August 8, 2001

Examiner: tbd

For: PHOTOCURABLE LIQUID RESIN COMPOSITION

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October 25, 2001

PRELIMINARY AMENDMENT

Hon. Commissioner of Patents
and Trademarks
Washington, D.C. 20231

Sir:

Prior to examination on the merits, please amend the application in the manner set forth below.

IN THE CLAIMS

Please cancel claims 3-18 and 20 without prejudice or disclaimer.

Please enter amended claims 1 and 19.

1. (Amended) A photocurable resin composition comprising:

- (A) an epoxy compound having two or more alicyclic epoxy groups;
- (B) a cationic photopolymerization initiator;
- (C) a combination of two or more ethylenically unsaturated polyfunctional monomers, said combination including
 - (i) a monomer derived from a pentaerythritol; and
 - (ii) bisphenol A diglycidyl ether with terminal (meth)acrylates;
- (D) a radical photopolymerization initiator; and
- (E) a polyether polyol compound having one or more hydroxyl groups in one molecule.